Layer-by-layer construction of electronic band topology

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Abstract: Layered quantum materials are building blocks to realize exotic topological physics. For instance, by programmably stacking magnetic MnBi₂Te₄ and non-magnetic Bi₂Te₃ layers, one can realize a plethora of fascinating topological quantum effects such as the quantum anomalous Hall effect (QAHE) and quantum spin Hall effect (QSHE). However, the realization of those effects in (MnBi₂Te₄)_m(Bi₂Te₃)_n has met tremendous challenges. In our 2DCC user project, we first employ time- and angle-resolved photoemission spectroscopy on bulk MnBi₂Te₄ [1], MnBi₄Te₇ [2], and MnBi₆Te₁₀ [3] to reveal the electronic origins of these challenges. Subsequently, we use molecular beam epitaxy to establish two-quintuple-layer Bi2Te3 films and MnBi2Te4/Bi2Te3 heterostructures as building blocks of the future with atomic-layer controlled thicknesses and a unique morphology: the films extend coherently over millimetre scales with minimal disruptions by the substrate step edges [4]. We reveal the digitally varied electronic structures of $(Bi_2Te_3)_n$ and $MnBi_2Te_4/(Bi_2Te_3)_n$ and reach excellent agreement with theoretical predictions layer-by-layer. By modulating the interlayer distance in two-quintuple-layer Bi2Te3 using time-resolved photoemission, we elucidate the perturbative band dynamics which suggests an inverted bandgap. This result is corroborated by scanning tunneling spectroscopy measurements unveiling edge states between topologically trivial and nontrivial areas. The inverted gaps of two-quintuple-layer Bi₂Te₃ films and MnBi₂Te₄/Bi₂Te₃ heterostructures are 100 and 150 meV, respectively, suggesting possibilities for near-ambient-temperature QSHE.

- [1] Nguyen et al. Science Advances 10, eadn5696 (2024)
- [2] Lee et al. Nature Physics 19, 950 (2023)
- [3] Nguyen et al. Nanoscale Advance Article (2025)
- [4] Lee et al. In Review (2025)